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NOTICE OF ALLOWANCE AND FEE(S) DUE

23685

7590

03/29/2004

KRIEGSMAN & KRIEGSMAN 665 FRANKLIN STREET FRAMINGHAM, MA 01702

EXAMINER STOCK JR, GORDON J

PAPER NUMBER

ART UNIT 2877 DATE MAILED: 03/29/2004

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/579,593	05/26/2000	Joseph J. Danko	81329A	8869

TITLE OF INVENTION: METHOD AND APPARATUS FOR INSPECTING A PATTERNED SEMICONDUCTOR WAFER

APPLN. TYPE	SMALL ENTITY	ISSUE FEE	PUBLICATION FEE	TOTAL FEE(S) DUE	DATE DUE
nonprovisional	NO	\$1330	\$0	\$1330	06/29/2004

THE APPLICATION IDENTIFIED ABOVE HAS BEEN EXAMINED AND IS ALLOWED FOR ISSUANCE AS A PATENT. PROSECUTION ON THE MERITS IS CLOSED. THIS NOTICE OF ALLOWANCE IS NOT A GRANT OF PATENT RIGHTS. THIS APPLICATION IS SUBJECT TO WITHDRAWAL FROM ISSUE AT THE INITIATIVE OF THE OFFICE OR UPON PETITION BY THE APPLICANT. SEE 37 CFR 1.313 AND MPEP 1308.

THE ISSUE FEE AND PUBLICATION FEE (IF REQUIRED) MUST BE PAID WITHIN THREE MONTHS FROM THE MAILING DATE OF THIS NOTICE OR THIS APPLICATION SHALL BE REGARDED AS ABANDONED. STATUTORY PERIOD CANNOT BE EXTENDED. SEE 35 U.S.C. 151. THE ISSUE FEE DUE INDICATED ABOVE REFLECTS A CREDIT FOR ANY PREVIOUSLY PAID ISSUE FEE APPLIED IN THIS APPLICATION. THE PTOL-85B (OR AN EQUIVALENT) MUST BE RETURNED WITHIN THIS PERIOD EVEN IF NO FEE IS DUE OR THE APPLICATION WILL BE REGARDED AS ABANDONED.

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- Applicant claims SMALL ENTITY status. See 37 CFR 1.27.
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- III. All communications regarding this application must give the application number. Please direct all communications prior to issuance to Mail Stop ISSUE FEE unless advised to the contrary.

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23685 7590 03/29/2004				papers. Each additio	nal paper, such as an assignme ate of mailing or transmission.	ent or formal drawing, must	
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						(Signature) (Date)	
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STOCK JR,	GORDON J	2877		356-237400	_		
Address form PTO/SB/12 "Fee Address" indicati PTO/SB/47; Rev 03-02 (Number is required. 3. ASSIGNEE NAME AND PLEASE NOTE: Unless	on (or "Fee Address" Indicated or more recent) attached. Use RESIDENCE DATA TO B an assignee is identified beld to the USPTO or is being s	ion form of a Customer E PRINTED ON Tow, no assignee dubmitted under se	agents OR, altern firm (having as a agent) and the nattorneys or agen will be printed. THE PATENT (print ata will appear on the parate cover. Comple	e patent. Inclusion of	e of a single d attorney or stered patent ed, no name 3 assignee data is only appropria of a substitute for filing an ass	ate when an assignment has ignment.	
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KRIEGSMA 665 FRANK				STOCK JR,	GORDON J
FRAMINGH		=		ART UNIT	PAPER NUMBER
				2877	
				DATE MAILED: 03/29/200-	4

Determination of Patent Term Extension under 35 U.S.C. 154 (b)

(application filed after June 7, 1995 but prior to May 29, 2000)

The Patent Term Extension is 0 day(s). Any patent to issue from the above-identified application will include an indication of the 0 day extension on the front page.

If a Continued Prosecution Application (CPA) was filed in the above-identified application, the filing date that determines Patent Term Extension is the filing date of the most recent CPA.

Applicant will be able to obtain more detailed information by accessing the Patent Application Information Retrieval (PAIR) system (http://pair.uspto.gov).

Any questions regarding the Patent Term Extension or Adjustment determination should be directed to the Office of Patent Legal Administration at (703) 305-1383. Questions relating to issue and publication fee payments should be directed to the Customer Service Center of the Office of Patent Publication at (703) 305-8283.

		\mathcal{N}^{TY}
	Application No.	Applicant(s)
	09/579,593	DANKO, JOSEPH J.
Notice of Allowability	Examiner	Art Unit
	Gordon J Stock	2877
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.31	6 (OR REMAINS) CLOSED in this ap) or other appropriate communicatio RIGHTS. This application is subject t	oplication. If not included n will be mailed in due course. THIS
1. $oxed{oxed}$ This communication is responsive to $\underline{correspondence\ filed}$	<u>d on 3/4/04</u> .	
2. ☑ The allowed claim(s) is/are <u>1-14 and 19-21</u> .		
3. \square The drawings filed on $___$ are accepted by the Examine	er.	
4. ☐ Acknowledgment is made of a claim for foreign priority u a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents hav 2. ☐ Certified copies of the priority documents hav 3. ☐ Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDON! THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. ☐ A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which giv 6. ☒ CORRECTED DRAWINGS (as "replacement sheets") mu (a) ☒ including changes required by the Notice of Draftsper 1) ☒ hereto or 2) ☐ to Paper No./Mail Date (b) ☒ including changes required by the attached Examiner Paper No./Mail Date 1/30/03. Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	re been received. re been received in Application No recurrents have been received in this recurrents have been received have been received have been received have been received hav	national stage application from the complying with the requirements R'S AMENDMENT or NOTICE OF ation is deficient. 9-948) attached Office action of ings in the front (not the back) of
DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT	osit of BIOLOGICAL MATERIAL	must be submitted. Note the
Attachment(s)		
1. Notice of References Cited (PTO-892)	<u> </u>	Patent Application (PTO-152)
2. ☑ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summar Paper No./Mail Da	
 Information Disclosure Statements (PTO-1449 or PTO/SB/ Paper No./Mail Date 		
4. Examiner's Comment Regarding Requirement for Deposit	-	ent of Reasons for Allowance
of Biological Material	9. ⊠ Other <u><i>PTOL-413B</i></u>	<u>attached</u> .

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Irving Kriegsman on March 15, 2004.

After an updated search, Examiner found U.S. Patent 6,288,780 to Fairley et al. read on claims 1, 3, and 19 (of after final amendment of March 4, 2004). Particularly, there was the potential of a 35 U.S.C. 102(e) rejection with respect to claims 1 and 3 and a 35 U.S.C. 103(a) rejection in view of U.S. Patent 6,091,488 to Bishop for claim 19. Thereby, the Examiner initiated an interview with attorney (see PTOL-413B attached). Examiner suggested cancellation of claims; however, attorney suggested amending of claims 1, 3, and 19 to overcome the possible rejections in regards to the Fairley reference and any other prior art by amending claims 1, 3, and 19 to have the claims read in regards to a single light source rather than possibly reading as two separate light sources producing two beams of light. Examiner agreed with a proposed amendment and agreed that the proposed amendment to the claims 1, 3, and 19 overcame any possible rejection with regards to U.S. Patent 6,288,780 to Fairley et al. and was made allowable over the prior art. Examiner agreed that the approved proposed amendment to claims 1, 3, and 19 would be made by Examiner's amendment. So after final amendment of March 4, 2004 will be entered; claims 1, 3, and 19 will be amended by Examiner's Amendment.

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In addition, Examiner has made a correction to claim 3 due to a typographical error: line 1 should read –contaminant-- rather than "contaminate." And a correction to claim 19 due to a typographical error has been made: line 7 should read --from-- rather than "form."

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The amended claims showing corrections are:

1.(currently amended) An apparatus for detecting the presence of contaminant particles on a surface of a semiconductor wafer having repetitive patterns, said apparatus comprising:

- (a) means for producing a first beam of light and a second beam of light, said means comprising a laser for producing a beam of laser light and a beamsplitter for splitting up the beam of laser light into said first beam of light and said second beam of light,
- (b) first optical means for illuminating a first region area on the semiconductor wafer with said first beam of light,
- (c) second optical means for illuminating a second region on the semiconductor wafer sample with said second beam of light,
- (d) said first beam of light striking the semiconductor wafer at a first approach angle which is angularly adjustable and a first angle of incidence which is angularly adjustable,
- (e) said second beam of light striking the semiconductor wafer at a second approach angle which is angularly adjustable and a second angle of incidence which is angularly adjustable,
- (f) said first approach angle and said first angle of incidence being adjustable independent of said second approach angle and said second angle of incidence, respectively,

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(g) an imaging detector disposed above the semiconductor wafer for detecting light scattered from the area illuminated but not specularly reflected light,

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- (h) an imaging lens for imaging said area illuminated on said imaging detector, said imaging lens having a Fourier plane, and
- (i) a spatial filter in the Fourier plane of the imaging lens for masking off the diffraction pattern produced by the background on the semiconductor wafer from each one of the two illuminating beams of light.
- 3.(currently amended) A method for detecting the presence of [contaminate] contaminant particles on a semiconductor wafer having repetitive patterns, said apparatus comprising:
- (a) illuminating a portion of the semiconductor wafer with first and second beams of light originating from a single light source,
- (b) said first beam of light striking the semiconductor wafer at a first approach angle which is angularly adjustable and a first angle of incidence which is angularly adjustable,
- (c) said second beam of light striking the semiconductor wafer at a second approach angle which is angularly adjustable and a second angle of incidence which is angularly adjustable,
- (d) said first approach angle and said first angle of incidence being adjustable independent of said second approach angle and said second angle of incidence, respectively,
 - (e) adjusting said first and second approach angles to minimize background scatter,
- (f) positioning an imaging detector above the semiconductor wafer for detecting at least some of the light scattered from the area illuminated but not specularly reflected light,

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(g) providing an imaging lens for imaging said area illuminated on said imaging detector, said imaging lens having a Fourier plane,

- (h) providing a spatial filter in the Fourier plane on the imaging lens for masking off the diffraction pattern produced by the background on the semiconductor wafer from a first one of the two beams of light, and
- (i) adjusting said angle of incidence of the other beam of light so that the diffraction pattern formed by the other beam of light in the Fourier plane overlaps the diffraction pattern formed by the first beam of light.
- 19.(currently amended) A method for detecting the presence of contaminant particles on a semiconductor wafer having repetitive patterns, said method comprising:
- (a) illuminating a pair of intersecting stripe shaped regions on the semiconductor wafer, using a pair of beams of light <u>originating from a single light source</u>, each beam of light having an approach angle and an angle of incidence that is angularly adjustable independent of the approach angle and angle of incidence of the other beam of light, and
- (b) detecting at least some of the light scattered [form] <u>from</u> the area illuminated but not specularly reflected light as said semiconductor wafer is moving using a lens and CCD camera having a square array sensor and operational in a time delayed integration mode.

Allowable Subject Matter

- 2. Claims 1-14, and 19-21 are allowed.
- 3. The following is an examiner's statement of reasons for allowance:

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As to claim 1, the prior art of record, taken alone or in combination, fails to disclose or render obvious the first approach and incident angles being adjustable independent of second approach and incident angles limitation in an apparatus for detecting the presence of contaminant particles on a semiconductor wafer and means for producing a first beam of light and a second beam of light, said means comprising a laser for producing a beam of laser light and a beamsplitter for splitting up the beam of laser light into said first beam of light and said second beam of light, in combination with the rest of the limitations of claim 1.

As to claim 2, the prior art of record, taken alone or in combination, fails to disclose or render obvious the first approach and incident angles being adjustable independent of second approach and incident angles limitation and the angularly movable first and second tower limitations in an apparatus for detecting the presence of contaminant particles on a semiconductor wafer, in combination with the rest of the limitations of claim 2.

As to claim 3, the prior art of record, taken alone or in combination, fails to disclose or render obvious the first approach and incident angles being adjustable independent of second approach and incident angles limitation in a method for detecting the presence of contaminant particles on a semiconductor wafer and illuminating a portion of the semiconductor wafer with first and second beams of light originating from a single light source, in combination with the rest of the limitations of claim 3.

As to **claim 4**, the prior art of record, taken alone or in combination, fails to disclose or render obvious the first approach and incident angles being adjustable independent of second approach and incident angles limitation in an apparatus for detecting the presence of contaminant particles on a semiconductor wafer, in combination with the rest of the limitations of **claim 4**.

As to claim 5, the prior art of record, taken alone or in combination, fails to disclose or render obvious the first and second tower being angularly movable limitations in an apparatus for detecting the presence of contaminant particles on a semiconductor wafer, in combination with the rest of the limitations of claims 5-10.

As to claim 11, the prior art of record, taken alone or in combination, fails to disclose or render obvious a light source adapted to produce a first beam of light and a second beam of light; a first approach angle which is angularly adjustable; a second approach angle which is angularly adjustable; a CCD camera being operational in a time delayed integration mode in an apparatus for detecting the presence of contaminant particles on a surface of a semiconductor wafer having repetitive patterns, in combination with the rest of the limitations of claims 11-14, 20 and 21.

Examiner would like to mention that **claims 20-21** were inadvertently overlooked in prior office action (see action of September 9, 2003) due to **claims 20-21** images not being indexed with the rest of the claims' images in correspondence of June 5, 2003. However, claims 20-21 depend from an allowed base claim. Therefore, they would have been allowed in the prior office action of September 9, 2003. Examiner apologizes for any inconvenience.

As to claim 19, the prior art of record, taken alone or in combination, fails to disclose or render obvious in a method for detecting the presence of contaminant particles on a semiconductor wafer having repetitive patterns illuminating a pair of intersecting stripe shaped regions on the semiconductor wafer, using a pair of beams of light originating from a single light source, each beam of light having an approach angle and an angle of incidence that is angularly adjustable independent of the approach angle and angle of incidence of the other beam of light, in combination with the rest of the limitations of claim 19.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

- 4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure:
 - U.S. Patent 6,366,352 to Goldberg et al.
 - U.S. Patent 6,587,193 to Reinhron et al.

Fax/Telephone Numbers

If the applicant wishes to send a fax dealing with either a proposed amendment or a discussion with a phone interview, then the fax should:

- 1) Contain either a statement "DRAFT" or "PROPOSED AMENDMENT" on the fax cover sheet; and
 - 2) Should be unsigned by the attorney or agent.

This will ensure that it will not be entered into the case and will be forwarded to the examiner as quickly as possible.

Papers related to the application may be submitted to Group 2800 by Fax transmission. Papers should be faxed to Group 2800 via the PTO Fax machine located in Crystal Plaza 4. The form of such papers must conform to the notice published in the Official Gazette, 1096 OG 30 (November 15, 1989). The CP4 Fax Machine number is: (703) 872-9306

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Gordon J. Stock whose telephone number is (571) 272-2431. The examiner can normally be reached on Monday-Friday, 8:00 a.m. - 4:30 p.m.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

Application/Control Number: 09/579,593

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gs March 15, 2004

Primary Examiner
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